

Supplementary information

WO₃ electrodes by spray pyrolysis for photoelectrochemical applications: Impact of W precursor and Cl incorporation

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Table S1. Comparison of photocurrents of WO₃ films prepared from AMT, PTA, WCl₆ in EtOH and WCl₆ in MeOH precursors at 1.4 V vs. Ag/AgCl under monochromatic illumination at 369 nm, 100 W/m².

Precursor solution	Layer thickness (μm)	Photocurrent density @ 1.4V vs. Ag/AgCl (mA/cm ²)
AMT	0.58	0.653
AMT	1.47	0.294
AMT + NH ₄ Cl (3 % Cl)	0.64	2.82
AMT + NH ₄ Cl (3 % Cl)	1.48	3.1
AMT + NH ₄ Cl (6 % Cl)	0.58	1.72
AMT + NH ₄ Cl (6 % Cl)	1.69	2
PTA	0.56	0.43
PTA	1.09	0.5
PTA	1.49	0.37
PTA	2.19	0.44
PTA	2.55	0.59
PTA	2.99	0.73
WCl ₆ in MeOH	0.51	1.08
WCl ₆ in MeOH	0.96	1.02
WCl ₆ in MeOH	1.11	1.02
WCl ₆ in EtOH	0.21	0.25
WCl ₆ in EtOH	0.46	0.29